L Number	Hits		DB	Time stamp
1	59	((() table (digital distribution)) bio	USPAT;	2003/11/21 15:40
_		and (root near mean near square near surface near roughness)	US-PGPUB; EPO; JPO; DERWENT	
2	18	(428/426,446,447.ccls. and ((((silicon near (dioxide oxide)) silica siO siO2 sio?sub.2) same (layer coating)) and (surface near roughness))) and (428/426,446,447.ccls. and ((((silicon near (dioxide oxide)) silica siO siO2 sio?sub.2) same (layer coating)) and haze)) and (428/426,446,447.ccls. and ((((silicon near (dioxide oxide)) silica siO siO2 sio?sub.2) same (layer coating)) and (humidity rh)))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/11/21 15:41
3	76	(((silicon near (dioxide oxide)) silica siO siO2 sio?sub.2) same (layer coating)) and (root near mean near square near surface near roughness)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/11/21 15:41
4	12	((sicl4 sicl?sub.4 (silicon near tetrachloride)) same (vapor gas)) same ((relative near humifity) rh!)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/11/21 15:41
5	33	((sicl4 sicl?sub.4 (silicon near tetrachloride)) same (vapor gas)) same ((humidity) rh!)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/11/21 15:41
6	72	428/426,446,447.ccls. and ((((silicon near (dioxide oxide)) silica siO siO2 sio?sub.2) same (layer coating)) same haze)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/11/21 15:42
7	99	(((silicon near (dioxide oxide)) silica siO siO2 sio?sub.2)) and (root near mean near square near surface near roughness)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/11/21 15:42
8	25	(((((silicon near (dioxide oxide)) silica siO siO2 sio?sub.2) same (layer coating)) and (surface near roughness)) and (vapor near (deposition deposited deposit depositing))) and (alkylchlorosilane dimethyldichlorosilane trimethylchlorosilane CH32Cl2Si CH32SiCl2 CH3cl3Si ch3sicl3 (ch?sub.3 near ?sub.2 near cl?sub.2 near Si) (ch?sub.3 near ?sub.2 near si near cl?sub.2) (ch?sub.3 near cl?sub.3 near si near cl?sub.3))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/11/21 15:43
9	129	((sicl4 sicl?sub.4 (silicon near tetrachloride)) same (vapor gas)) and (((((silicon near (dioxide oxide)) silica siO siO2 sio?sub.2) same (layer coating)) and (surface near roughness)) and (vapor near (deposition deposited deposit depositing)))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/11/21 15:43
10	59	(((silicon near (dioxide oxide)) siO siO2 sio?sub.2) same (layer coating)) and (root near mean near square near surface near roughness)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/11/21 15:43
11	76	(((silicon near (dioxide oxide)) silica siO siO2 sio?sub.2) same (layer coating)) and (root near mean near square near surface near roughness)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/11/21 15:44
12	18	(428/426,446,447.ccls. and ((((silicon near (dioxide oxide)) silica siO siO2 sio?sub.2) same (layer coating)) and (surface near roughness))) and (428/426,446,447.ccls. and ((((silicon near (dioxide oxide)) silica siO siO2 sio?sub.2) same (layer coating)) and haze)) and (428/426,446,447.ccls. and ((((silicon near (dioxide oxide)) silica siO siO2 sio?sub.2) same (layer coating)) and (humidity rh)))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/11/21 15:44
13	12	((sicl4 sicl?sub.4 (silicon near tetrachloride)) same (vapor gas)) same ((relative near humifity) rh!)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/11/21 15:44
14	33	((sicl4 sicl?sub.4 (silicon near tetrachloride)) same (vapor gas)) same ((humidity) rh!)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/11/21 15:44

15	72	428/426,446,447.ccls. and ((((silicon near (dioxide oxide)) silica siO	USPAT,	2003/11/21 15:44
1		siO2 sio?sub.2) same (layer coating)) same haze)	US-PGPUB;	
			EPO; JPO;	
			DERWENT	
16	99	(((silicon near (dioxide oxide)) silica siO siO2 sio?sub.2)) and (root near	USPAT;	2003/11/21 15:44
}		mean near square near surface near roughness)	US-PGPUB;	
1			EPO; JPO;	
			DERWENT	
17	25	(((((silicon near (dioxide oxide)) silica siO siO2 sio?sub.2) same (layer	USPAT;	2003/11/21 15:45
1		coating)) and (surface near roughness)) and (vapor near (deposition	US-PGPUB;	
1		deposited deposit depositing))) and (alkylchlorosilane	EPO; JPO;	
		dimethyldichlorosilane trimethylchlorosilane CH32Cl2Si CH32SiCl2	DERWENT	
		CH3cl3Si ch3sicl3 (ch?sub.3 near ?sub.2 near cl?sub.2 near Si) (ch?sub.3		
		near ?sub.2 near si near cl?sub.2) (ch?sub.3 near cl?sub.3 near si)		
10	1,00	(ch?sub.3 near si near cl?sub.3))	TIOD I T	0000/11/01 15 45
18	129	((sicl4 sicl?sub.4 (silicon near tetrachloride)) same (vapor gas)) and	USPAT;	2003/11/21 15:45
		((((((silicon near (dioxide oxide)) silica siO siO2 sio?sub.2) same (layer	US-PGPUB;	
		coating)) and (surface near roughness)) and (vapor near (deposition	EPO; JPO;	
L		deposited deposit depositing)))	DERWENT	

19	34	(((((silicon near (dioxide oxide)) siO siO2 sio?sub.2) same (layer	USPAT;	2003/11/21 15:45
		coating)) and (root near mean near square near surface near roughness))	US-PGPUB;	
		((428/426,446,447.ccls. and ((((silicon near (dioxide oxide)) silica siO	EPO; JPO;	
		siO2 sio?sub.2) same (layer coating)) and (surface near roughness))) and	DERWENT	
		(428/426,446,447.ccls. and ((((silicon near (dioxide oxide)) silica siO		
		siO2 sio?sub.2) same (layer coating)) and haze)) and		
		(428/426,446,447.ccls. and ((((silicon near (dioxide oxide)) silica siO		
		siO2 sio?sub.2) same (layer coating)) and (humidity rh)))) ((((silicon		
		near (dioxide oxide)) silica siO siO2 sio?sub.2) same (layer coating)) and		
		(root near mean near square near surface near roughness)) (((sicl4		
		sicl?sub.4 (silicon near tetrachloride)) same (vapor gas)) same ((relative		
		near humifity) rh!)) (((sicl4 sicl?sub.4 (silicon near tetrachloride)) same		
		(vapor gas)) same ((humidity) rh!)) (428/426,446,447.ccls. and		
		((((silicon near (dioxide oxide)) silica siO siO2 sio?sub.2) same (layer		ļ
		coating)) same haze)) ((((silicon near (dioxide oxide)) silica siO siO2		
		sio?sub.2)) and (root near mean near square near surface near roughness)		
) ((((((silicon near (dioxide oxide)) silica siO siO2 sio?sub.2) same (layer		
İ		coating)) and (surface near roughness)) and (vapor near (deposition		
		deposited deposit depositing))) and (alkylchlorosilane		
		dimethyldichlorosilane trimethylchlorosilane CH32Cl2Si CH32SiCl2		
		CH3cl3Si ch3sicl3 (ch?sub.3 near ?sub.2 near cl?sub.2 near Si) (ch?sub.3		
		near ?sub.2 near si near cl?sub.2) (ch?sub.3 near cl?sub.3 near si)		
		(ch?sub.3 near si near cl?sub.3)))(((sicl4 sicl?sub.4 (silicon near		
		tetrachloride)) same (vapor gas)) and (((((silicon near (dioxide oxide))		
1		silica siO siO2 sio?sub.2) same (layer coating)) and (surface near		
		roughness)) and (vapor near (deposition deposited deposit depositing))))		
		((((silicon near (dioxide oxide)) siO siO2 sio?sub.2) same (layer coating))		
		and (root near mean near square near surface near roughness)) ((((silicon		
		near (dioxide oxide)) silica siO siO2 sio?sub.2) same (layer coating)) and		
		(root near mean near square near surface near roughness))		
		((428/426,446,447.ccls. and ((((silicon near (dioxide oxide)) silica siO		
		siO2 sio?sub.2) same (layer coating)) and (surface near roughness))) and		
		(428/426,446,447.ccls. and ((((silicon near (dioxide oxide)) silica siO		
		siO2 sio?sub.2) same (layer coating)) and haze)) and		
		(428/426,446,447.ccls. and ((((silicon near (dioxide oxide)) silica siO		
		siO2 sio?sub.2) same (layer coating)) and (humidity rh)))) (((sicl4)		
		sicl?sub.4 (silicon near tetrachloride)) same (vapor gas)) same ((relative		
		near humifity) rh!)) (((sicl4 sicl?sub.4 (silicon near tetrachloride)) same		
		(vapor gas)) same ((humidity) rh!)) (428/426,446,447.ccls. and		
	!	((((silicon near (dioxide oxide)) silica siO siO2 sio?sub.2) same (layer		
		coating)) same haze)) ((((silicon near (dioxide oxide)) silica siO siO2		
		sio?sub.2)) and (root near mean near square near surface near roughness)		
) ((((((silicon near (dioxide oxide)) silica siO siO2 sio?sub.2) same (layer		
		coating)) and (surface near roughness)) and (vapor near (deposition		
		deposited deposit depositing))) and (alkylchlorosilane		
		dimethyldichlorosilane trimethylchlorosilane CH32Cl2Si CH32SiCl2		
		CH3cl3Si ch3sicl3 (ch?sub.3 near ?sub.2 near cl?sub.2 near Si) (ch?sub.3		
		near ?sub.2 near si near cl?sub.2) (ch?sub.3 near cl?sub.3 near si)		
		(ch?sub.3 near si near cl?sub.3))) (((sicl4 sicl?sub.4 (silicon near		
		tetrachloride)) same (vapor gas)) and (((((silicon near (dioxide oxide))		
		silica siO siO2 sio?sub.2) same (layer coating)) and (surface near		
		roughness)) and (vapor near (deposition deposited deposit depositing)))		
)) and @pd>20030616		